

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Annapragada et al.

Application Serial No.: 10/712,326

Filed: November 12, 2003

Title: Minimizing the Loss of Barrier

Materials During Photoresist

Stripping

Materials During Photoresist

Ofroup Art Unit: 2813

Examiner: Nguyen, Thanh T

Materials During Photoresist

Ofroup Art Unit: 2813

## RESPONSE TO FINAL OFFICE ACTION

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir/Madam:

In response to a final office action mailed April 25, 2006 in the above-referenced patent application, please amend the application as follows under the provision of 37 C.F.R. §1.116(a). Allowance of pending claims 1-21 in view of the following amendments and remarks is respectfully requested.

**Amendments to the Claims** are reflected in the listing of claims which begins on Page 2 of this paper.

Remarks begin on page 9.